

New Non-Reinforced Substrates for use as Embedded Capacitors

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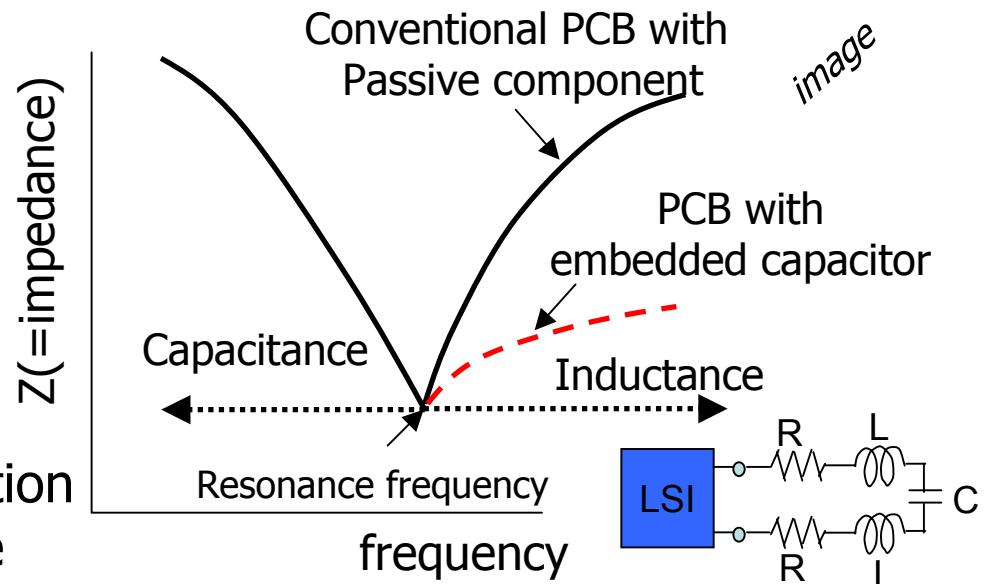


Background-1

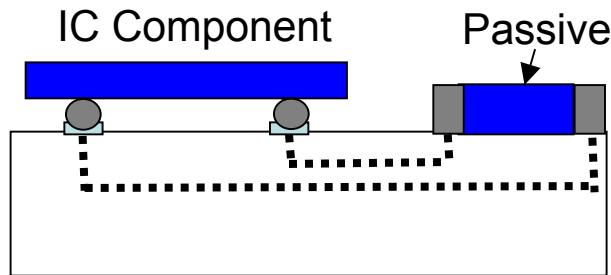
Current application
with Embedded Capacitor

- Hi-end computers
- Network servers
- Network routers

→ Demand for power distribution
system with low impedance

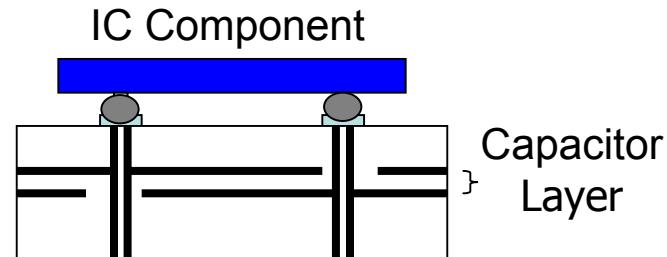


Conventional PCB



High Inductance

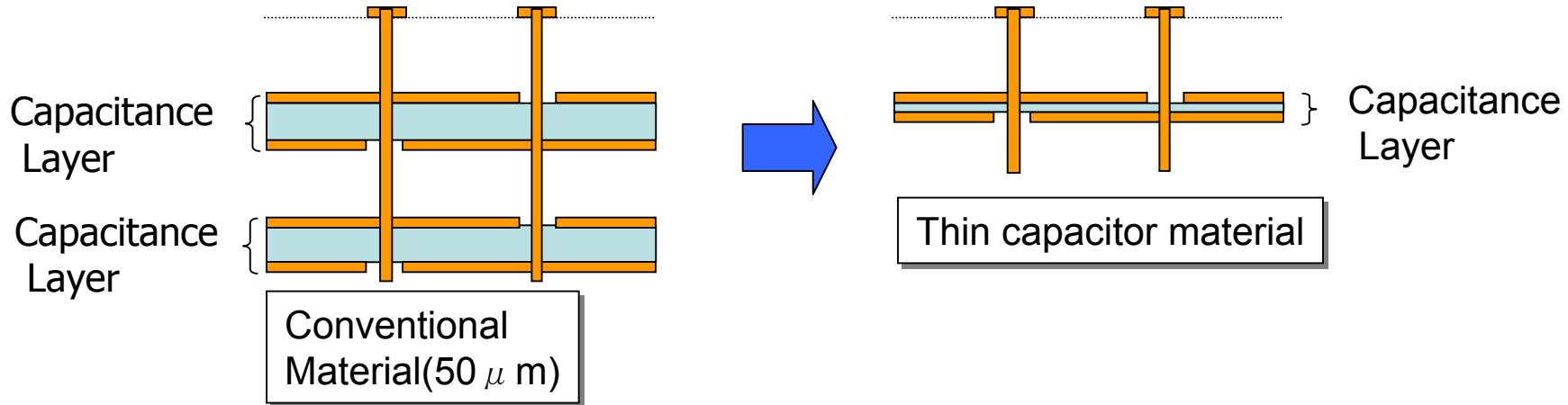
PWB with capacitor



Low Inductance

Background-2

PWB with capacitor



Demand for Thin(<25micron) Capacitor Material

Expectation by using Thin Capacitor Material

- Improvement in electrical performance
- Reduce cost
- Reduce thickness of the board

Development of Thin Capacitor & Investigations

Material Selection to Construct **Thin Capacitor**

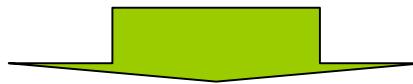
- a) Copper Foil b) Dielectric Resin



Characterization of **Thin Capacitor**

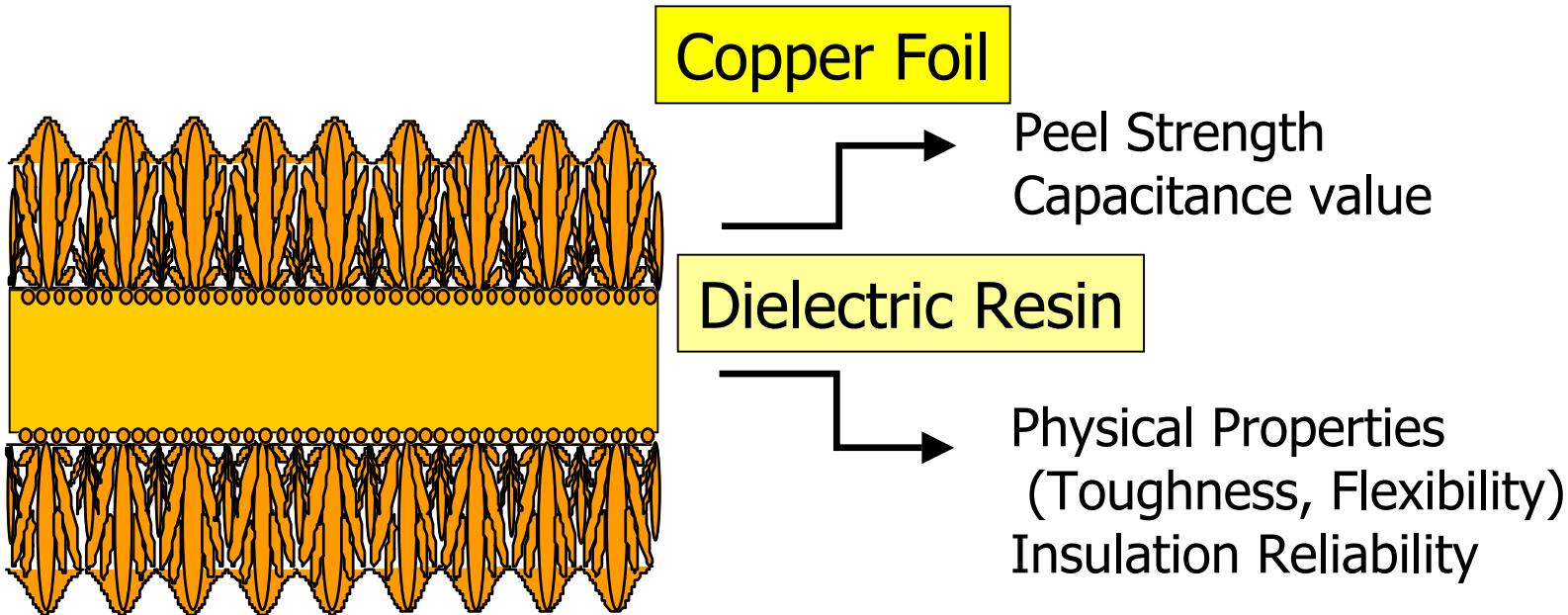


PWB Manufacturing Processing
of **Thin Capacitor**



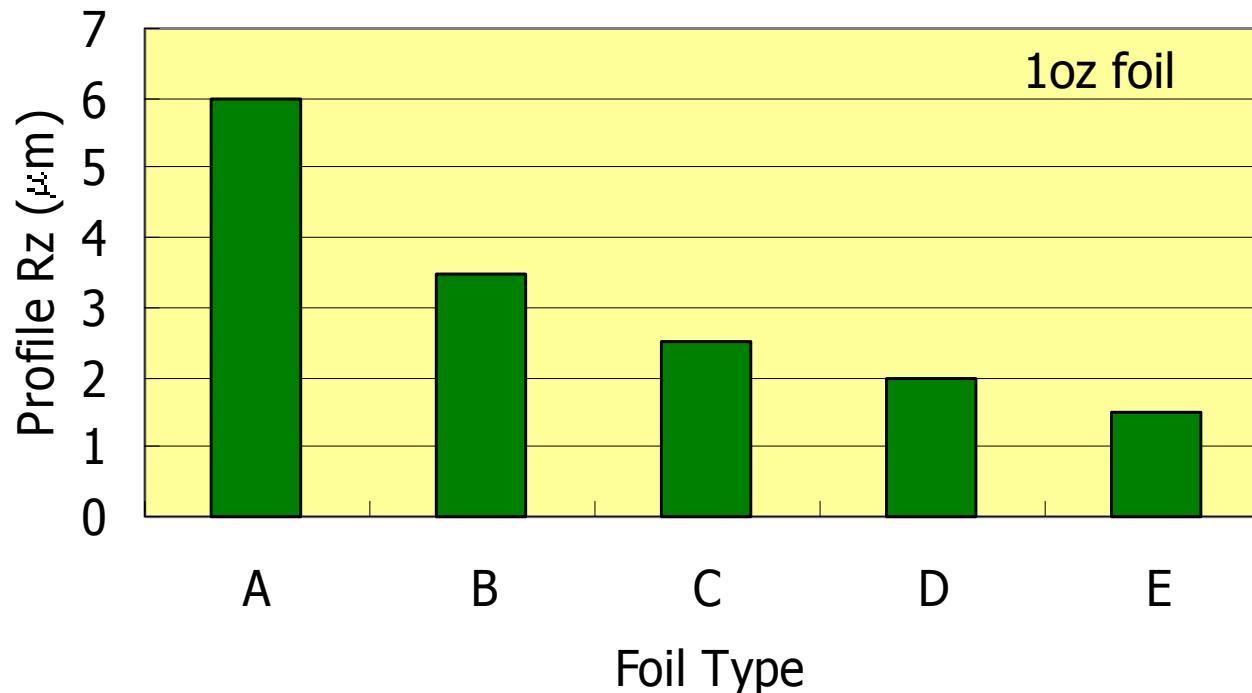
Decoupling Performance of PWBs using
Thin Capacitor Material

Thin capacitor material



Copper Foil - Profile(1)

- A) Standard HTE electro deposited (ED) copper foil
- B) RTF(Reverse treated foil)
- C) Super low profile ED foil
- D) Ultra low profile ED foil
- E) Wrought foil



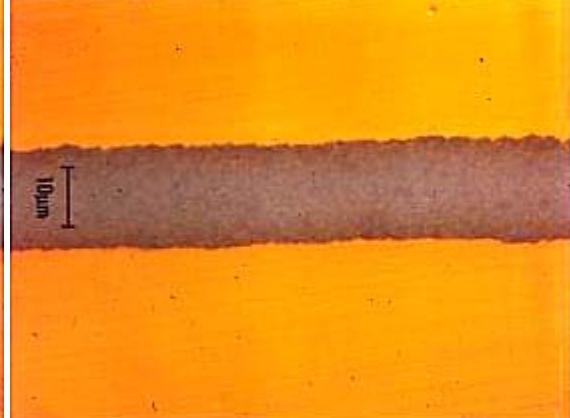
Copper Foil - Profile(2)



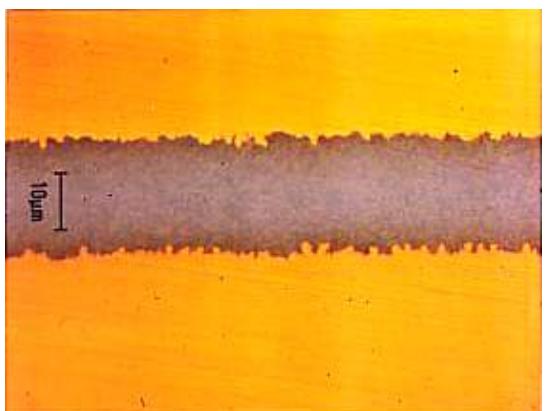
Foil E $Rz=1.5 \mu\text{m}$



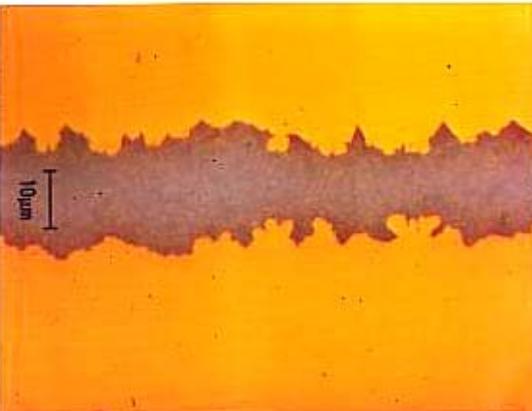
Foil D $Rz=2.0 \mu\text{m}$



Foil C $Rz=2.5 \mu\text{m}$



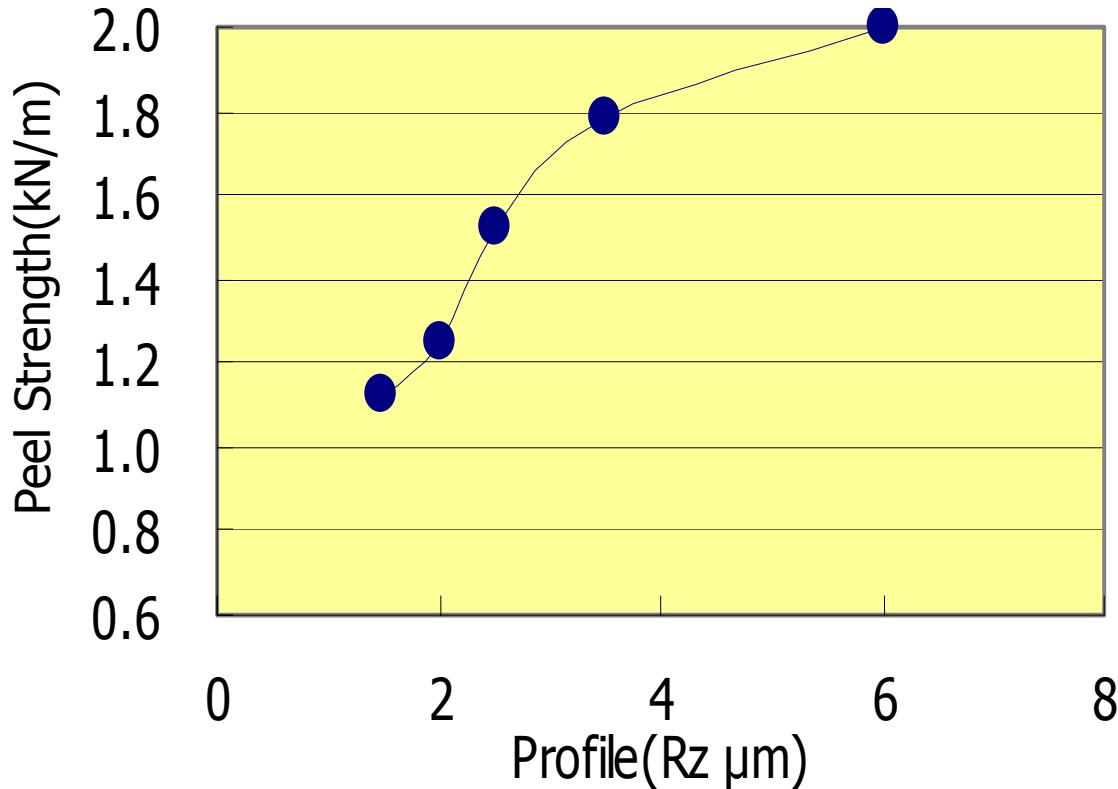
Foil B $Rz=3.5 \mu\text{m}$



Foil A $Rz=6.0 \mu\text{m}$

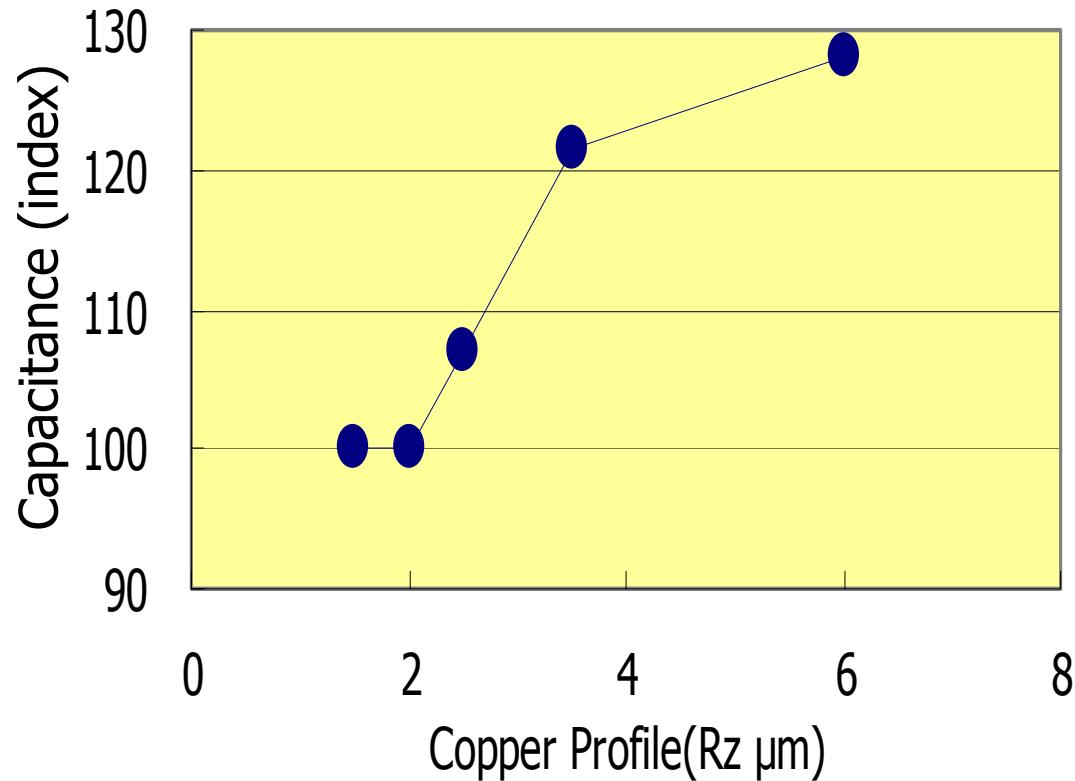
Capacitor were formed with 20micron dielectric thickness using various copper foils.

Copper Foil - Peel strength



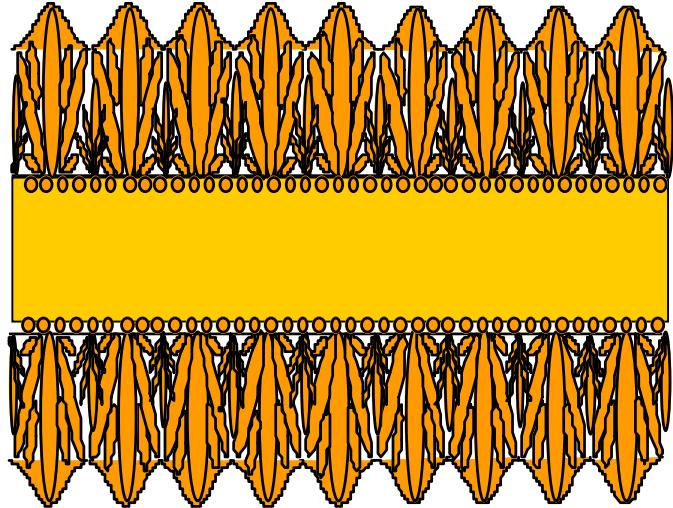
Measured on standard epoxy resin system.
1oz copper foil.

Copper Foil - Capacitance



Dielectric thickness 20micron.
Measured frequency 1MHz
Measured diameter 20mm

Thin capacitor material - Dielectric Resin



Dielectric Resin

Physical Properties
(Toughness, Flexibility)
Insulation Reliability

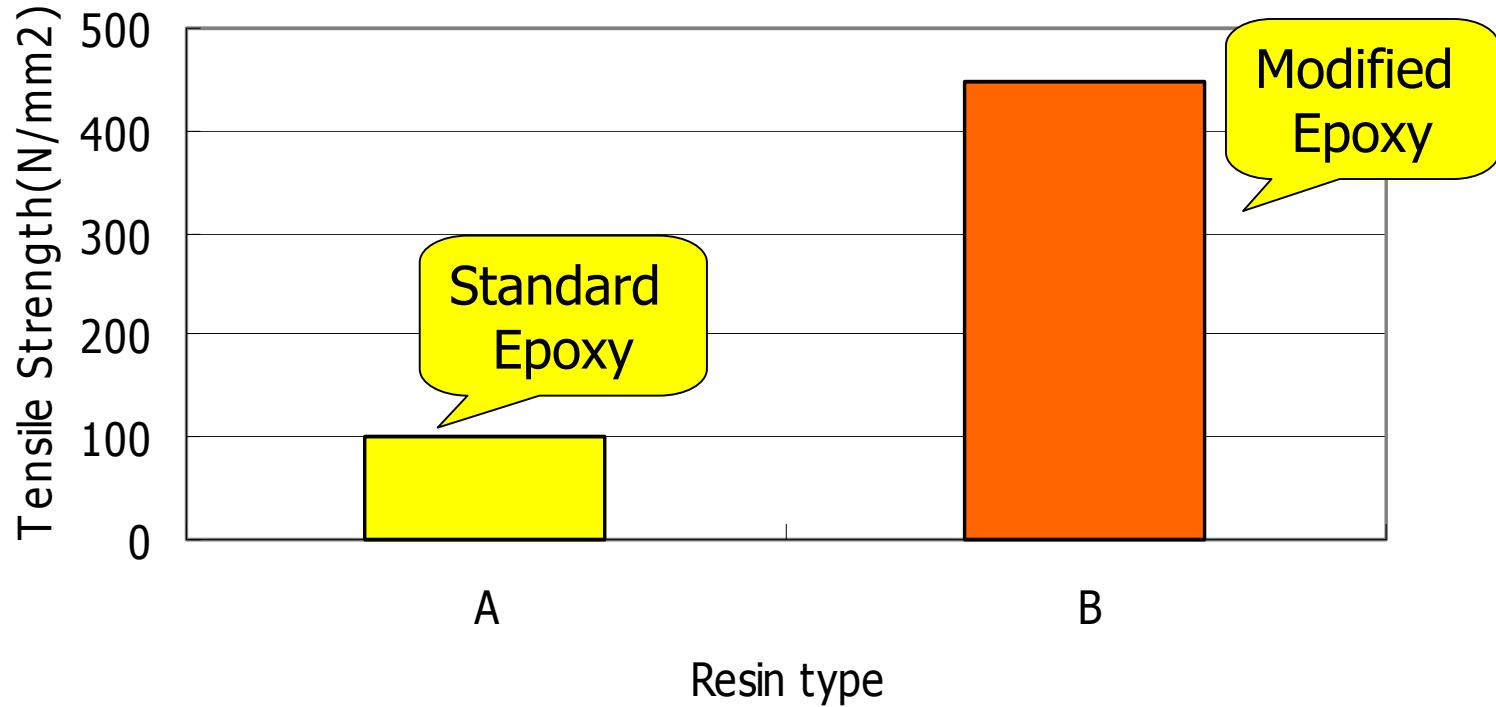
Prepared dielectric for evaluation :

Type A : Standard Epoxy

Type B : Modified Epoxy



Dielectric Resin - Tensile Strength

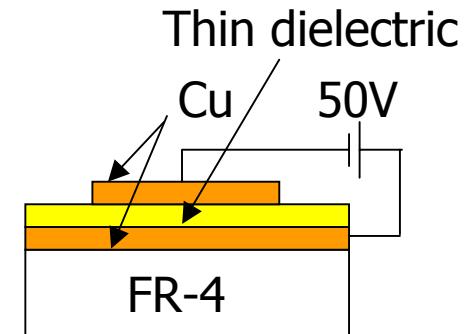
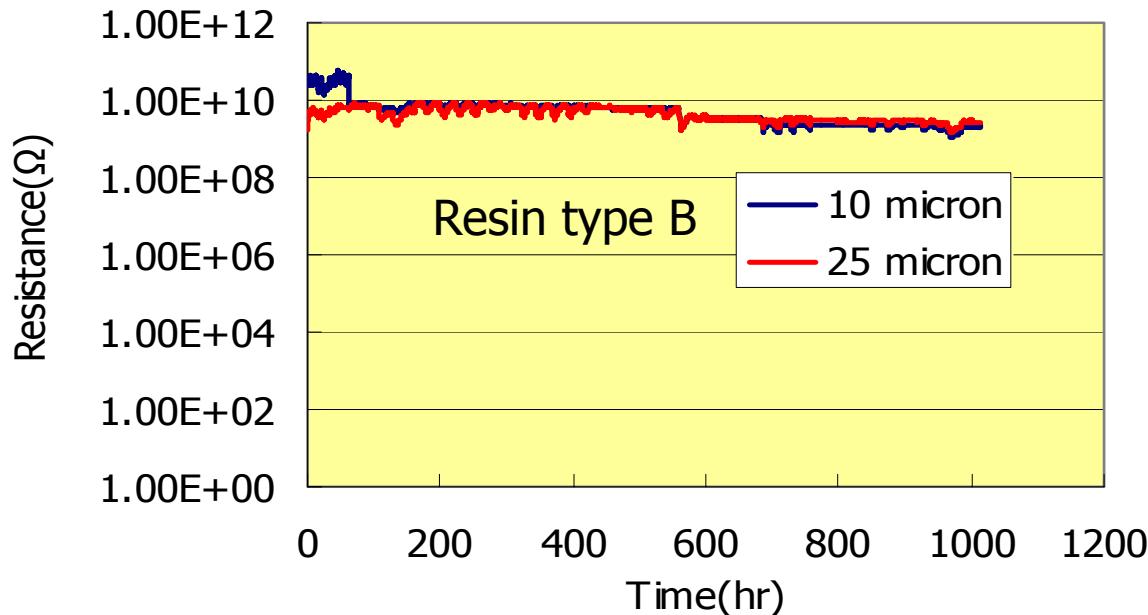


Resin Type	A	B
Tensile Strength* (N/mm ²)	99	448

* Measured on 10µm thick resin

Dielectric Resin - Electro Migration

Test condition: 85C/85% 50V



Electro migration test

Resin type	Lasted hours		
	N=1	N=2	Avg.
A	658	706	682
B	>1000	>1000	>1000

Thin Capacitor Material Construction

Selection of copper foil and dielectric resin

Consideration

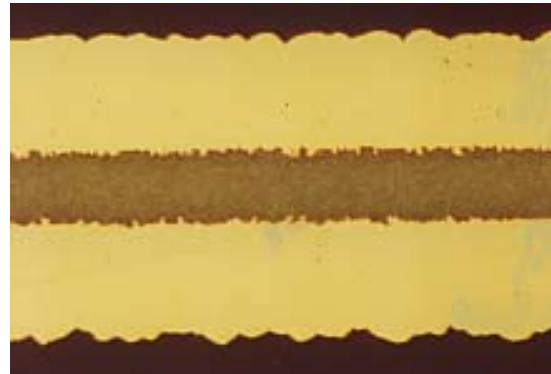
Copper Foil

Peel strength

High pot test yield

Capacitance

Dielectric thickness 25 μm Capacitor



→ Copper Foil **TypeB**

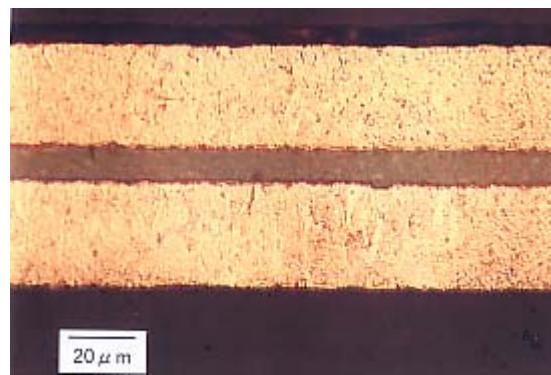
→ Dielectric resin **TypeB**

Dielectric Resin

Electro Migration

Toughness/Flexibility

Dielectric thickness 10 μm Capacitor



→ Copper Foil **TypeC**

→ Dielectric resin **TypeB**

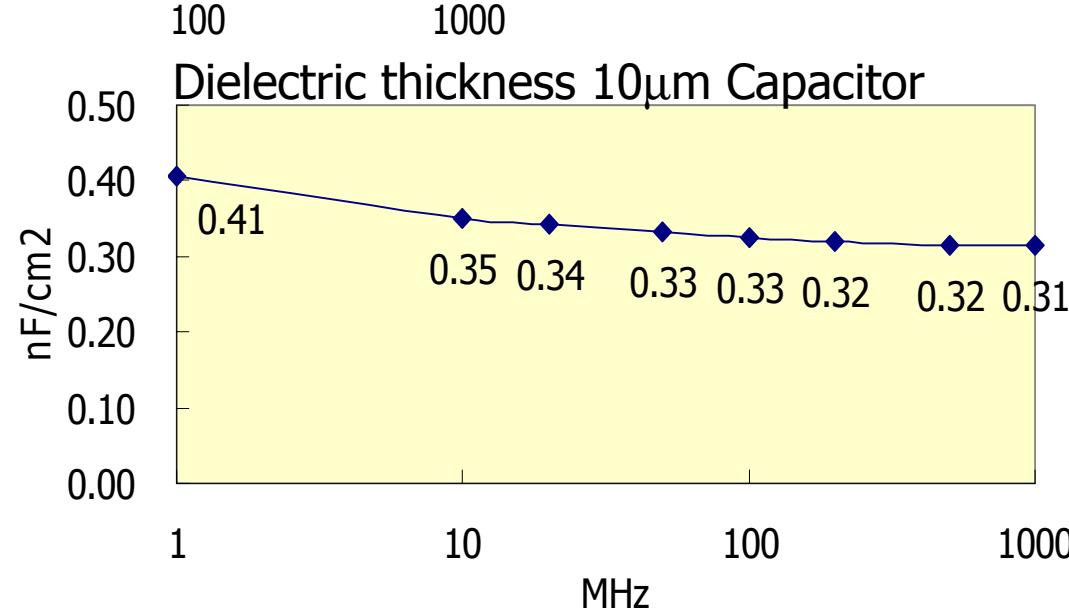
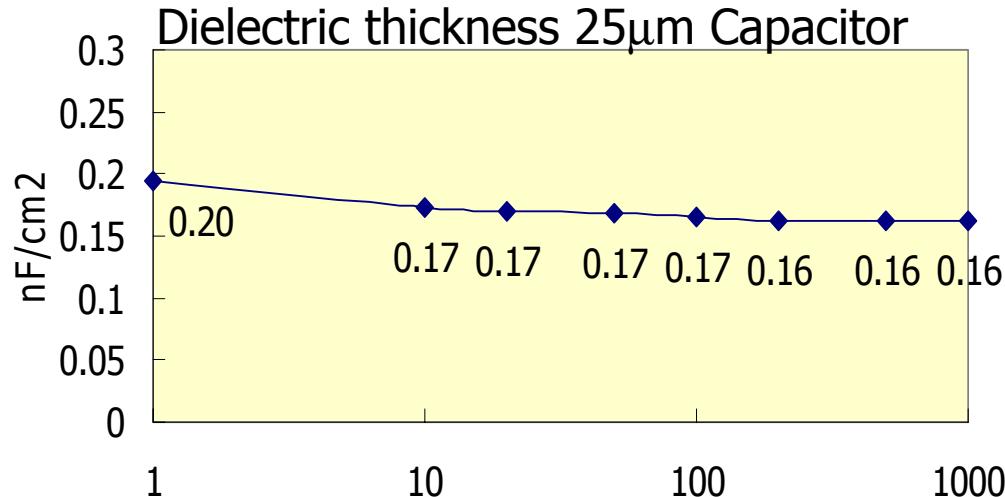
Thin Capacitor Material Characteristics

Thin capacitor characteristics

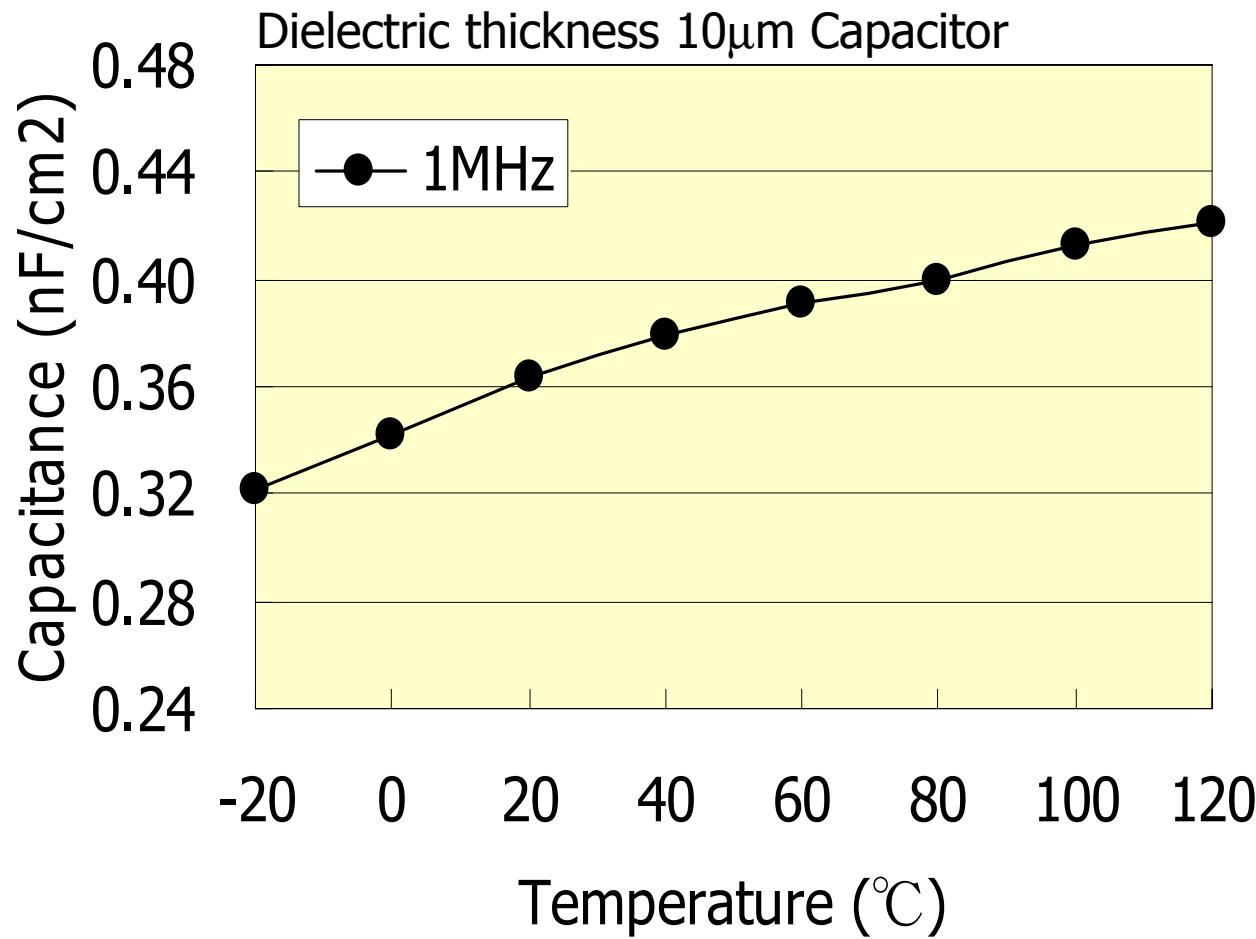
Properties	25µm Material	10µm Material
Copper foil type	B	C
Dielectric type	B	B
Copper weight (oz)	1	1
Peel strength (kN/m)	>1.0	>1.0
Dielectric thickness µm	25	10
Capacitance(nF/cm ²)10MHz	0.16	0.35
D _k at 10MHz	4.0	4.0
D _f at 10MHz	0.03	0.03
Dielectric breakdown V	>500	>500
T _g (DMA) Celsius	>220	>220
Electrical migration*(hrs)	>1000	>1000
Solder float (288Cx5times)	Passed	Passed

*RH85%/85C/50V

Frequency Characteristic - Capacitance

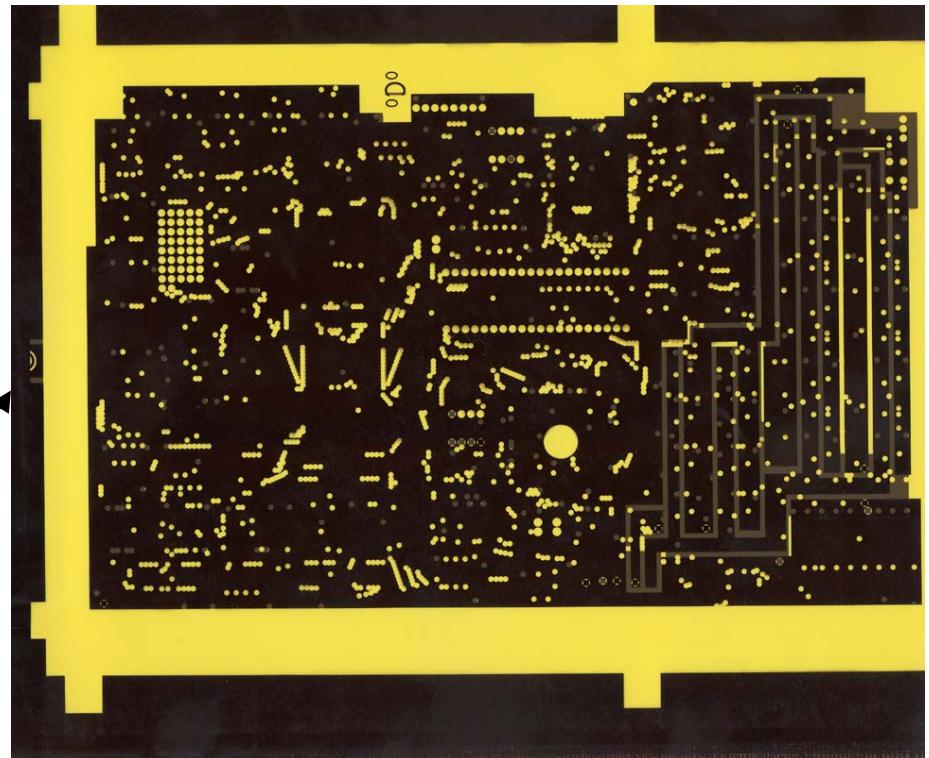
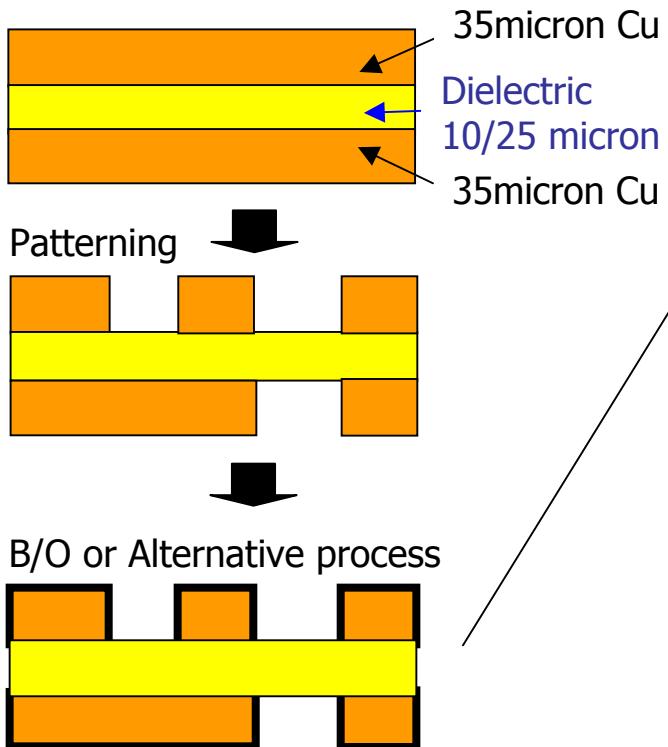


Temperature Characteristic - Capacitance

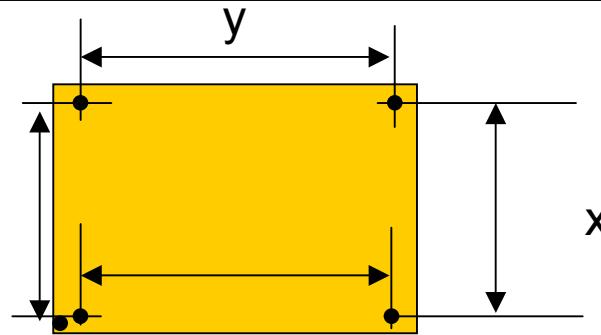


PWB Manufacturing Process

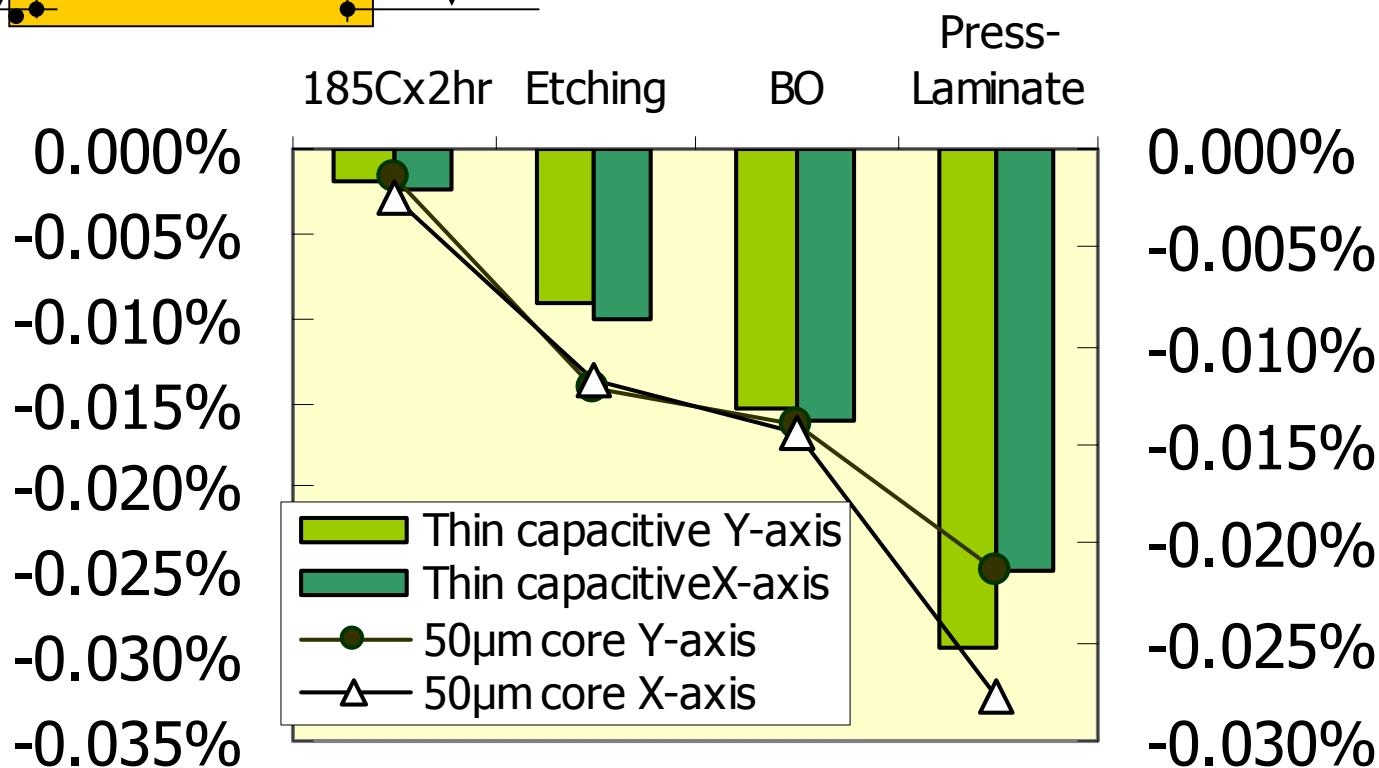
1. Chemical etching
2. Dry Film lamination
3. Image transfer
4. Pattern etching (Dual sides)
5. Black oxidizing



PWB Manufacturing Process - Scaling factor

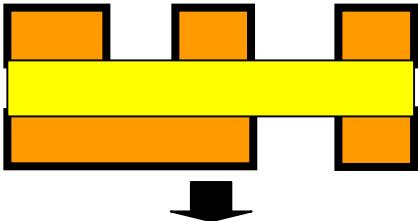


Dielectric thickness 10 μm Capacitor

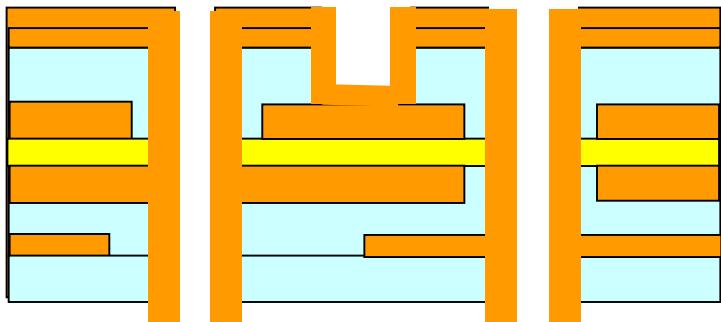


PWB Manufacturing Process - Lamination etc

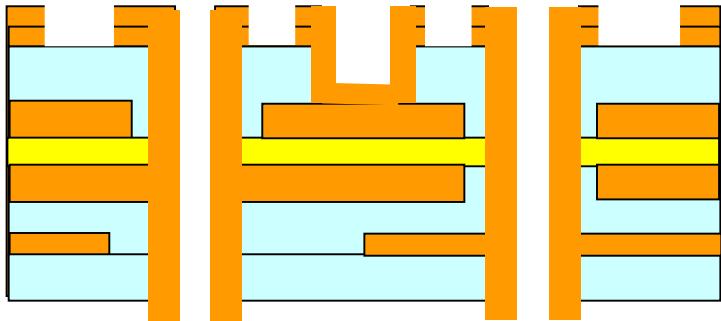
B/O or Alternative process



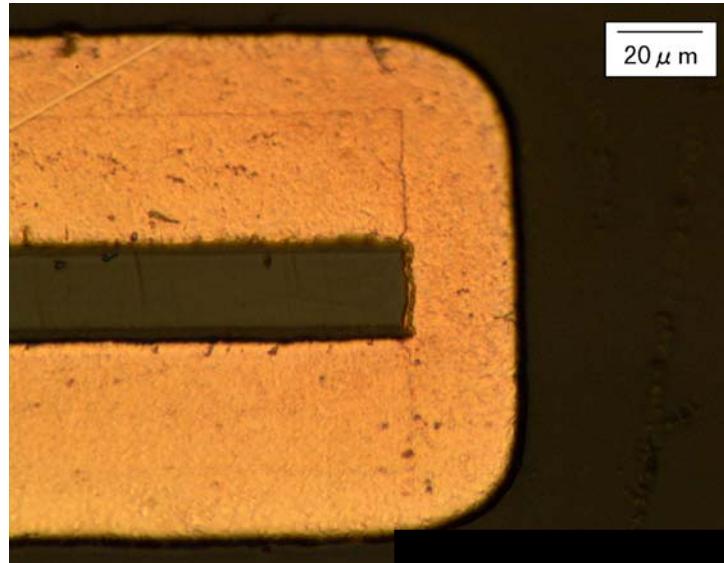
Through hole and Micro via formation



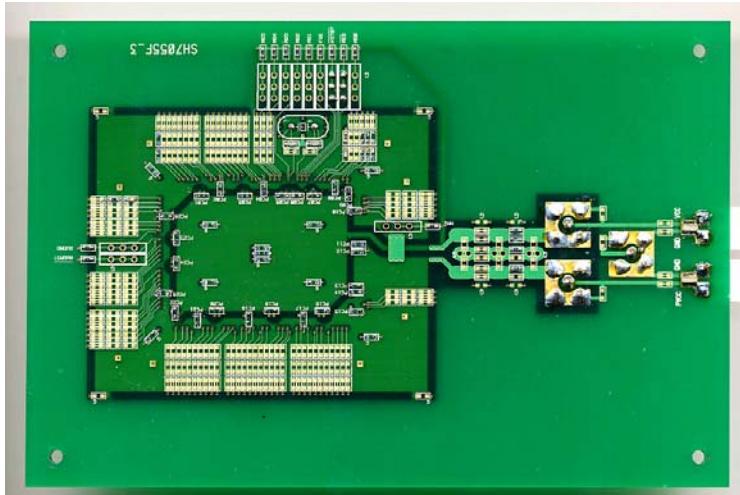
Patterning



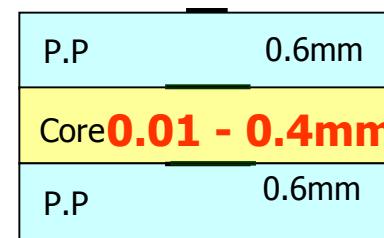
After Processing drilling,desmear and plating.



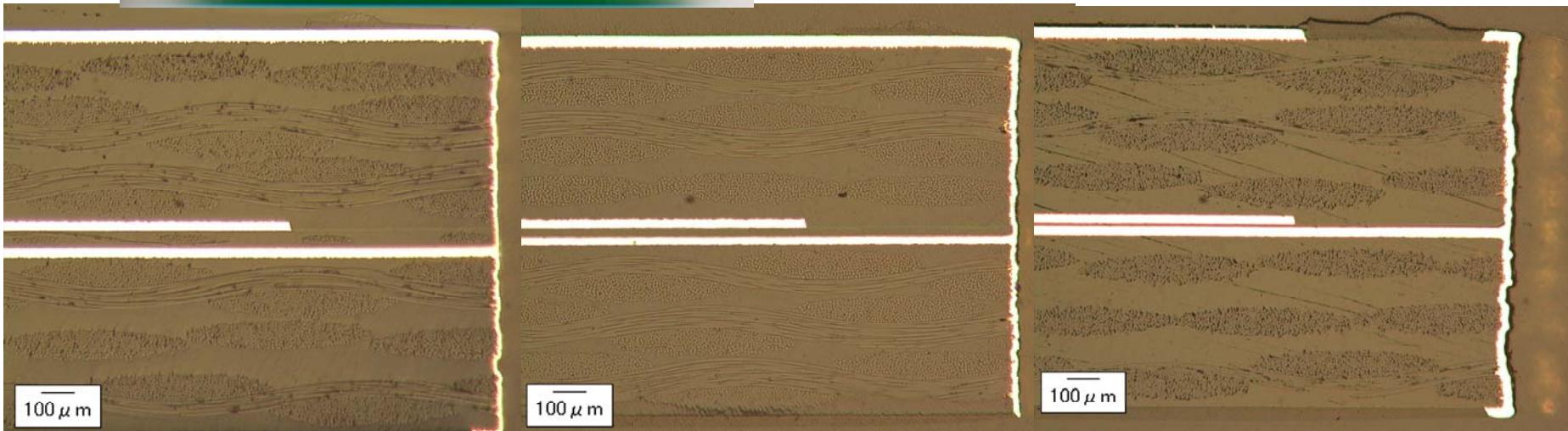
Comparison of PWB - Decoupling characteristics



4 layer board



L1
L2
L3
L4



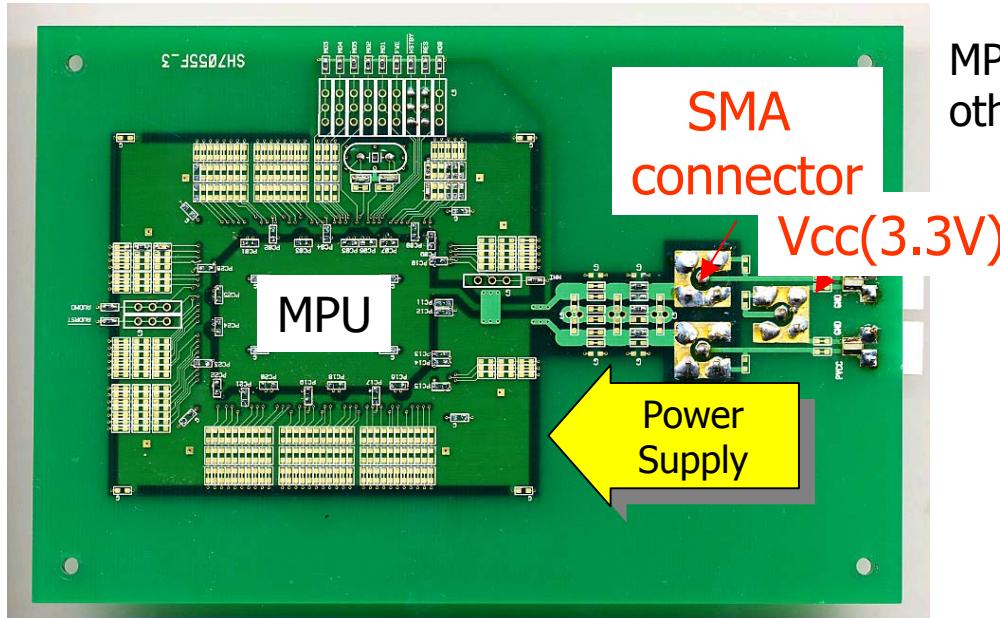
50 μ m core as a reference

25 μ m capacitor material

10 μ m capacitor material

Noise Measurement

Conducted Emission measurement by VDE method

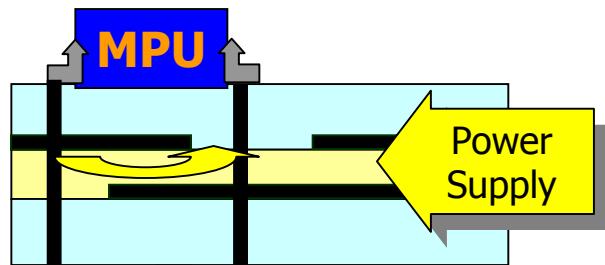


MPU(40MHz) is mounted on the other side of the board.

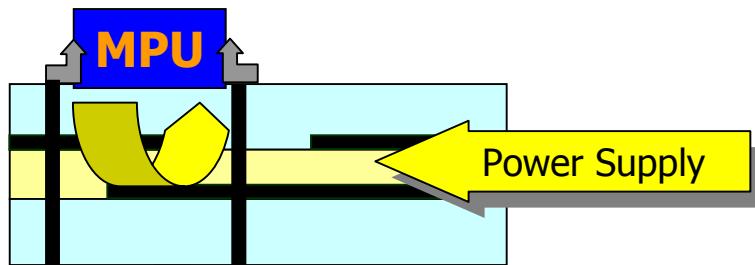
Construction

P.P	0.6mm
Core	0.01 - 0.4mm
P.P	0.6mm

L1
L2
L3
L4

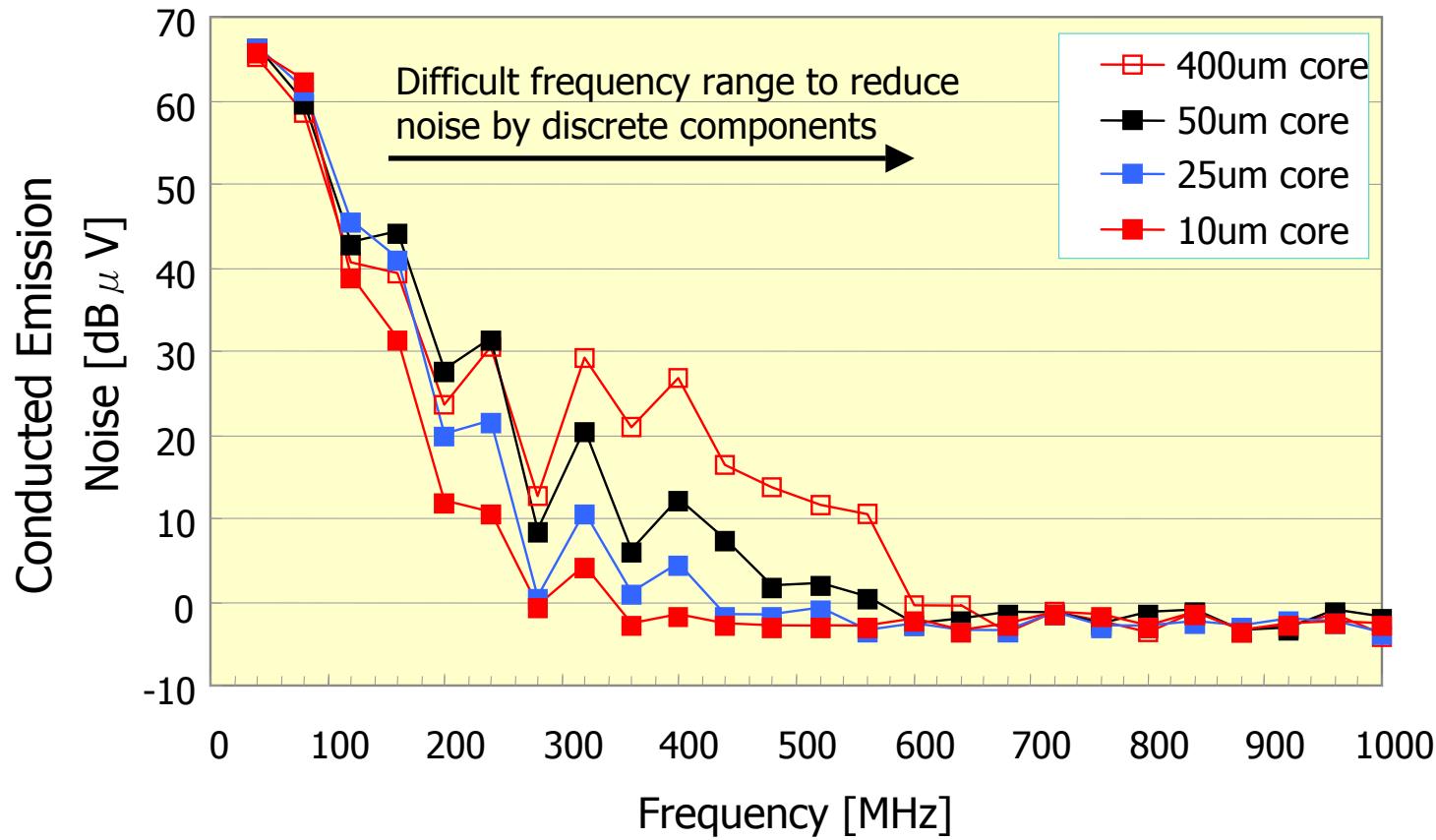


With poor decoupling characteristics



With good decoupling characteristics

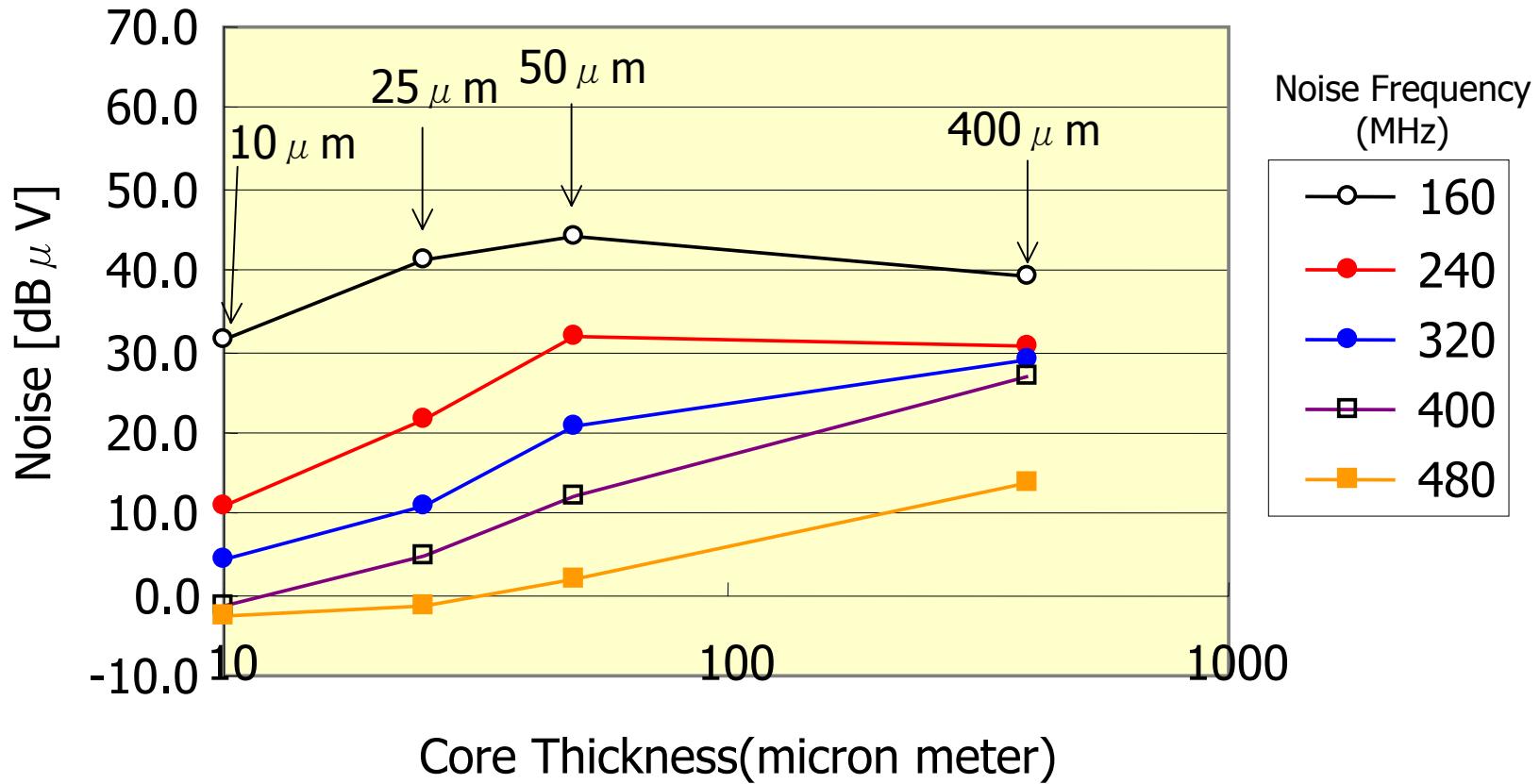
Noise Measurement



Significant noise reduction on PWBs
using thin capacitor layer

*Courtesy of HITACHI LTD.

Noise Measurement



The thinner the capacitance layer
the more efficient the noise reduction

Conclusion

- Contribution of copper foil and dielectric resin properties has been investigated.
Selection of copper and resin properties are important to construct Thin Capacitor material
 - Characteristics of thin capacitor has been investigated.
Characteristics of thin capacitor showed
 - Thin capacitor was capable to process through conventional PCB manufacturing process.
 - Improvements in performance as decoupling capacitor using thin capacitor material has been demonstrated.
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